

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

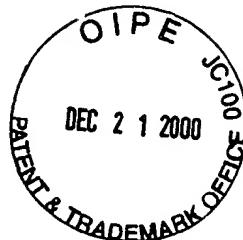
In re the Application of:

**Yosuke SHIRATA**

Serial Number: **09/684,898**

Filed: **October 10, 2000**

For: **LITHOGRAPHY SYSTEM AND METHOD**



Group Art Unit: **2851**

Examiner: **NGUYEN, H (Expected)**

Director of Patents and Trademarks  
Washington, D.C. 20231

**RECEIVED**

**PRELIMINARY AMENDMENT**

DEC 27 2000

TECHNOLOGY CENTER 2800

December 21, 2000

Dear Sir:

The following amendments and remarks are respectfully submitted.

**IN THE CLAIMS:**

Please **CANCEL** claims 9, 16 and 18 without prejudice or disclaimer.

Please **AMEND** claims as follows:

1. (Amended) A lithography system [including] comprising:  
an exposure apparatus which [exposes] projects a pattern on to a substrate [to project a pattern onto it] on which resist is coated [, and];  
a substrate processing apparatus connected to said exposure apparatus [and adapted to process] which processes the substrate [, the system comprising:];

Pre Andt B  
RABeep  
1/10/01